

High Fidelity Electron Beam Lithography for Photonic Devices

Martin KIRCHNER

Raith GmbH Dortmund, Germany

Electron beam lithography is a well-established method to define photonic elements. Waveguides, gratings and photonic crystals are important building blocks for many photonic devices. However the traditional way of electron beam lithography comes along with stitching errors reducing device performance. The presentation will review some innovative writing techniques, which help to write devices without stitching errors.

Long abstract not available at the date of final printing.

